# Superconductivity above H<sub>C2</sub> as a probe for Niobium RF-cavity surfaces

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-Volume characterization -Surface characterization:  $\cdot \chi(H, H_{AC}, \omega, T) \Rightarrow H_{C3}$  $\cdot M(H) \Rightarrow J_{C}$ 

-Summary + Conclusions



E. Maxwell & M. Strongin, PRL, 1963

Inversion routine J. Kötzler et al., PRL, 1994

● RRR 300(50)

### Upper critical field: H<sub>C2</sub>



#### Nucleation of surface superconductivity

![](_page_5_Figure_1.jpeg)

## Temperature variation of H<sub>C3</sub>

![](_page_6_Figure_1.jpeg)

![](_page_7_Figure_0.jpeg)

 $G = 2a\sigma$ 

![](_page_8_Figure_0.jpeg)

![](_page_9_Figure_0.jpeg)

![](_page_10_Figure_0.jpeg)

#### Gradient technique

Surface critical current density  $M = M_{c} + \chi H$   $M_{c} = J_{c}$ 

![](_page_11_Figure_2.jpeg)

![](_page_12_Figure_0.jpeg)

$$M_{C}(H) = M_{C}(H_{C2}) \left(\frac{H_{C3}^{C} - H}{H_{C3}^{C} - H_{C2}}\right)^{\alpha}$$
$$M_{C}(H_{C2}) = \pm \eta H_{C,th} \left(\frac{2\lambda}{R}\right)^{1/2} G\left(\frac{H}{H_{C2}}\right)$$

Fink & Barnes, PRL, 1965

![](_page_12_Figure_3.jpeg)

# $H_{C3}/H_{C2}$

Saint-James & de Gennes	GL	C,Cbe	Cb	Е	Eb	B	CS F	lu & Korema Phys. Rev., 1	n, 969
	1.695	1.86(3)	2.16(3)	2.10(3)	2.57(2)	1.925	5.2	2	
Naive model: $H_{C3}$ increases if the coherence length at the surface decreases => if the normal electrons mean free path $\ell$ at the surface decreases									
Model by Shmidt (Moscow:Nauka),1967				impurities in a layer of thickness d					
κ <sub>s</sub>	↓	$d \leq \xi_V$	$\frac{H_{c3}}{H_{c2}}$	-=1.67 (1+	(1-χ(ξ <sub>0</sub> /	ℓ))√1.7	$\frac{d}{\xi_{V}}$	$\frac{H_{C3}}{H_{C2}} \leq$	3.8
$\kappa_V$					C,Cbe	Cb	Е	Eb	
$\chi(\xi_0 / \ell) = \frac{\kappa}{\kappa}$	Gor '	kov, JETP, 1	960	$\chi(\xi_0 / I) \leq$	0.91	0.77	0.80	0.59	
dirty	$\chi_{\ell} \cong \chi_{\ell \to 0}$	$1.33 \frac{\ell}{\xi_0} \rightarrow 0$	)	dirty d(nm)≥	2.5	6.5	6	12	
clean	$\chi_\ell \cong 1$	$1-0.884 \frac{\xi}{\ell}$	<u>o</u> 2 C	lean ℓ(nm))	≤ 436	169	192	92	

Dirty:  $H_{C3}$  increases if d increases Clean:  $H_{C3}$  increases if  $\ell$  decreases

![](_page_14_Figure_0.jpeg)

C(μK) 72.3(1) 100.6(7) 40.2(3) 71.0(1) 48.3(4)

![](_page_15_Figure_0.jpeg)

Electropolishing: increase of  $H_{C3}$ 

increase  $J_c \Rightarrow$  stronger coupling across grain boundaries

Baking:increase  $H_{C3} =>$  decrease of the normal electron mean free path<br/>at the surface => impurities inclusion<br/>no change of  $J_C =>$  grain boundary coupling unchanged

#### **Open questions**

magnitude of C frequency dependence might help to study weak links

# Surface critical field H<sub>C3</sub>

![](_page_16_Figure_1.jpeg)